

Title (en)
SILVER BASED PHOTOMASKS

Title (de)
AUF SILBER BASIERENDE PHOTOMASKEN

Title (fr)
PHOTOMASQUES A BASE D'ARGENT

Publication
EP 1092173 A1 20010418 (EN)

Application
EP 99923736 A 19990528

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Abstract (en)
[origin: WO9963406A1] In the field of semiconductor photomask manufacture there is a need to produce photomasks more rapidly and with fewer flaws. There is also a need for photomasks capable of producing much finer resolution circuits than hitherto. There is disclosed a method of manufacturing a photomask (10) in which a substrate (11) is coated with an emulsion of gelatin (18) and a photosensitive silver halide (17). On exposure to an electron beam (15) or a laser beam, controlled to generate a desired pattern of movement, the silver halide reduces to create a photomask (10) after development and fixing.

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